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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Applicant

Hiroaki Niimi, et al.

Docket Number: TI-32705

Serial No.: 09/885,744

Art Unit: 2823

Filed: 06/20/01

Examiner: Khiem D. Nguyen

For: Method for Annealing Ultra-Thin, High Quality Gate Oxide

Layers Using Oxidizer/Hydrogen Mixtures

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Karen Vert

11-19-03

FACSIMILE COVER SHEET

| 1 | | |
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| X FACSIMILE COVER NEW APPLICATION DECLARATION ASSIGNMENT FORMAL DRAWING INFORMAL DRAWIN CONTINUATION API DIVISIONAL APP'N | s IGS | AMENDMENT (# Pages) EOT X NOTICE OF APPEAL APPEAL (# Pages) ISSUE FEE & PUBLICATION FEE (1 Page) REPLY BRIEF (IN TRIPLICATE) (# Pages) ELECTION |
| NAME OF INVENTOR(S): | | RECEIPT DATE & SERIAL NO.: |
| Hiroaki Niimi et al. | | Serial No.: 09/885,744 |
| TITLE OF INVENTION: Method for Annealing Ultra-Thin, High Quality Gete Oxide Layers Using Oxidizer/Hydrogen Mixtures | | Filing Date: 06/20/01 |
| TI FILE NO.: | DEPOSIT ACCT, NO.: | |
| TI-32705 | 20-0668 | |
| FAXED: 11-19-03 DUE: 11-19-03 ATTY/SECY: GCH/kjv | | |

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Texas instruments incorporated PO Box 655474, M/S 3999 Dallas, TX 75265-5474

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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NOTICE OF APPEAL FROM THE PRIMARY EXAMINER TO THE BOARD OF APPEALS

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

P.O. Box 655474, MS 3999 Dallas, TX 75265 (972) 470-0130 CERTIFICATION OF FACSIMILE TRANSMISSION certify that the following papers are being transmitted

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Sir:

Karen Viert

11-19-03

Applicants hereby appeal to the Board of Appeals from the decision dated <u>August 19, 2003</u> of the Primary Examiner finally rejecting claims <u>1-7 and 9-13</u>.

| | The iter | m(s) chec | xed below are appropriate: |
|--------------------------------|------------|-----------|--|
| 1. | | An exte | nsion of time to respond to the final rejection |
| | | | was granted on |
| | | | is requested for month(s). |
| 2. | | A timel | y response to the final rejection has been filed, as provided in 841 O.G. 1411. |
| 3. | _X_ | Fee \$33 | 0.00: |
| | | | Not required (Fee paid in prior appeal) |
| | | _X_ | The Commissioner of Patents is hereby authorized to charge any fees which may be required, or credit any overpayment to Deposit Account No. 20-0668 of Texas Instruments Incorporated. This form is submitted in triplicate. |
| Signat | ture [Rule | 191(b)] | Garle. Honorcutt |
| | | | hich correspondence is to be sent) Reg. No. 20,250 |
| Texas Instruments Incorporated | | | rated Attorney for Appellants |